

Atty. Dkt. No.	M#	Client Ref.
	306882	P-1741.000-US

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant:	Bob STREEFKERK <i>et al.</i>
Appln. No.:	TO BE ASSIGNED
Filing Date:	November 24, 2003
Examiner:	Unknown
Group Art Unit:	Unknown

Date: November 24, 2003 Page 1 of 3

**U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR 3,573,975	04/1971	Dhaka <i>et al.</i>	117	212	
	BR 3,648,587	03/1972	Stevens	95	44	
	CR 4,346,164	08/1982	Tabarelli <i>et al.</i>	430	311	
	DR 4,396,705	08/1983	Akeyama <i>et al.</i>	430	326	
	ER 4,480,910	11/1984	Takanashi <i>et al.</i>	355	30	
	FR 4,509,852	04/1985	Tabarelli <i>et al.</i>	355	30	
	GR 4,983,251	01/1991	Haisma <i>et al.</i>	156	630	
	HR 5,054,683	10/1991	Haisma <i>et al.</i>	228	198	
	IR 5,040,020	08/1991	Rauschenbach <i>et al.</i>	355	53	
	JR 5,121,256	06/1992	Corle <i>et al.</i>	359	664	
	KR 5,610,683	03/1997	Takahashi	355	53	
	LR 5,715,039	02/1998	Fukuda <i>et al.</i>	355	53	
	MR 5,825,043	10/1998	Suwa	250	548	
	NR 5,900,354	05/1999	Batchelder	430	395	

**FOREIGN PATENT DOCUMENTS**

	Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
	OR WO 99/49504	09/1999	PCT	Fukami <i>et al.</i>		X		X	
	PR EP 0023231	02/1981	Europe	Tabarelli <i>et al.</i>		X			
	QR EP 0418427	03/1991	Europe	Miyake		X		X	
	RR EP 1039511	09/2000	Europe	Murakimi <i>et al.</i>		X		X	
	SR DD 224448	07/1985	German	Hesse <i>et al.</i>			X		
	TR DD 242880	02/1987	German	Kuch			X		
	UR FR 2474708	07/1981	France	Letellier			X		
	VR JP 62-065326	03/1987	Japan	Moriuchi		X			
	WR JP 62-121417	06/1987	Japan	Nakazawa		X			
	XR JP 63-157419	06/1988	Japan	Nakasuji		X			

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

YR	EP Search Report for EP 02257938 dated September 25, 2003				
ZR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001				
AAR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356				
BBR	M. Switkes <i>et al.</i> , "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002				

Examiner: \_\_\_\_\_ Date Considered: \_\_\_\_\_

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)  
To: U.S. Department of Commerce  
(PW FORM PAT-1449)  
Patent and Trademark Office

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of

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Examiner: Unknown

Group Art Unit: Unknown

## **U.S. PATENT DOCUMENTS**

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	CCR	6,190,778	02/2001	Batz-Sohn <i>et al.</i>	428	448	
	DDR	6,191,429	02/2001	Suwa	250	548	
	EER	6,560,032	05/2003	Hatano	359	656	
	FFR	6,603,130	08/2003	Bisschops <i>et al.</i>	250	492.1	
	GGR	6,633,365	10/2003	Suenaga	355	53	
	HHR	2002/0163629	11/2002	Switkes <i>et al.</i>	355	53	
	IIR	2003/0123040	07/2003	Almoggy	355	69	
	JJR	2003/0174408	09/2003	Rostalski <i>et al.</i>	359	642	
	KKR						
	LLR						
	MMR						
	NNR						
	OOR						
	PPR						
	QQR						

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		Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
							Enclosed	No	Enclose	No
	RRR	JP 04-305915	10/1992	Japan	Ozeki <i>et al.</i>		X			
	SSR	JP 04-305917	10/1992	Japan	Ozeki <i>et al.</i>		X			
	TTR	JP 06-124873	05/1994	Japan	Takahashi		X		X	
	UUR	JP 07-220990	08/1995	Japan	Fukuda <i>et al.</i>		X			
	VVR	JP 10-228661	08/1998	Japan	Kurokawa		X			
	WWR	JP 10-255319	09/1998	Japan	Suenaga <i>et al.</i>		X			
	XXR	JP 10-303114	11/1998	Japan	Suwa		X		X	
	YYR	JP 10-340846	12/1998	Japan	Kudo		X		X	
	ZZR	JP 2001-091849	04/2001	Japan	Aizaki <i>et al.</i>		X			
	AAAR									

## **OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

	BBBR	B.J. Lin, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002			
	CCCC	B.J. Lin, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997			

Examiner

Date Considered:

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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DDD						
EEE						
FFF						

**FOREIGN PATENT DOCUMENTS**

ORIGINAL PAPER DOCUMENT							Abstract		Readily Available	
		Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No	Enclose	No
	GGG									
	HHH									

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

IIIR	B.J. Lin, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269				
JJJR	G.W.W. Stevens, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72				
KKK	S. Owa et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003				
LLL	S. Owa et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)				
MMM	Nikon Precision Europe GmbH, "Investor Relations – Nikon's Real Solutions", May 15, 2003				
NNN	H. Kawata et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36				
OOO	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309				
PPP	B.W. Smith et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003				
QQQ	H. Kawata et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177				
RRR	G. Owen et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036				
SSS					
TTT					
UUU					
VVV					
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XXX					
YYY					
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